

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Gabric et al.	Docket No.:	INF 2006 VJ 33543 US
Serial No.:	10/586,788	Art Unit:	2893
Filed:	September 2, 2008	Examiner:	Yushin, Nikolay K.
For:	Plasma Excited Chemical Vapor Deposition Method Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly		

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT ACCOMPANYING RCE

Dear Sir:

Applicant respectfully submits the following amendments and remarks in conjunction with a Request for Continued Examination and in response to the final Office Action dated November 4, 2009 and Advisory Action dated January 25, 2010. Applicant respectfully requests that the amendments and remarks presented herein be entered, and respectfully requests reconsideration of the claims.